

ABSTRACT

A method for manufacturing a disk substrate for mass production of a phase change optical disk, wherein an original disk substrate is having a resist layer (2) applied on a glass substrate (1), composed of the steps of forming a depression (pit "p1" and groove "g1") having a first and a second depth by cutting laser to be exposed on the surface of the resist layer (2), etching the depression having the first depth and the second depth from the surface of the resist layer (2) of the disk substrate in atmosphere mixed with Argon and Oxygen in ratio of 10 to 90% under gas pressure of 0.1 to 1.5 Pa, wherein the first and the second depth of the depression (pit "p1" and groove "g1") become predetermined value respectively, and ashing the resist layer (2) from the glass substrate (1).